



IT21

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:  
Syn-Ming Jang, et al.

Serial No. 10/062,314

Filed: February 1, 2002

For: HARD MASKING METHOD FOR  
FORMING PATTERNED OXYGEN  
CONTAINING PLASMA  
ETCHABLE LAYER

§ Attorney Docket No.  
1997-0306R / 24061.257  
§  
§ Customer No. 42717  
§  
§ Group Art Unit: 1754  
§  
§ Examiner: Cam N. Nguyen  
§ Notice of Allowance Mailed:  
January 31, 2005  
§  
§ Conf. No.: 3998

Mail Stop Issue Fee  
Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

### COMMENT ON STATEMENT OF REASONS FOR ALLOWANCE

Applicants acknowledge receipt of the Notice of Allowance mailed on January 31, 2005, which was accompanied by a Notice of Allowability (Form PTO-37). Page 2 of the Notice of Allowability sets forth a statement by the Examiner of reasons for allowing the claims. Applicants agree that the claims recite allowable subject matter. However, Applicants do not agree in all respects with the statement of reasons for allowance. For example, Applicants respectfully submit that the stated reasons should not be interpreted to mean that there are no other reasons which separately and independently support the allowability of the independent claims and/or the dependent claims.

Respectfully submitted,

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Enclosures: Acknowledgement Postcard

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450

on April 19, 2005  
  
Kelly A. Moreau